



[10191/3964]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : Franz LAERMER et al.
Serial No. : 10/530,612
Filed : December 30, 2005
For : **PLASMA SYSTEM AND METHOD FOR
ANISOTROPICALLY ETCHING STRUCTURES
INTO A SUBSTRATE**

Art Unit : 1792
Examiner : Maki A. Angadi
Confirmation No. : 6739

Mail Stop RCE
Commissioner for Patents
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Date: April 15, 2008

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Signature:

Richard M. Rosati

SUBMISSION ACCOMPANYING RCE UNDER 37 C.F.R. § 1.114

SIR:

This submission accompanies the filing of a Request for Continued Examination (RCE) in response to an October 16, 2007 Final Office Action in the above-identified application. Please reconsider, without prejudice, the above-captioned application as follows.

Remarks begin on page 2 of this paper.